Form PTO 1449 U.S. DEPAR MENT OF COMMERCE ATTY DOCKET NO. (Modified) PATENT AND FRADEMARK OFFICE 211147US99

SERIAL NO. 09/903,784

211147US99 APPLICANT

LIST OF REI	ST OF REFERENCES CITED BY APPLICANT			APPLICANT AROON TUNGARE ET AL			
			IOAIII	FILING DATE		GROUP	
· · · · · · · · · · · · · · · · · · ·				JULY 13, 2001		2826	
EXAMINER	т-	DOCUMENT		U.S. PATENT DOCUMENTS			
INITIAL		NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
FE_	AA	3,802,967	04/09/74	Ladany et al.		05.00	II AI FROFRIATE
	АВ	4,174,422	11/13/79	Matthews et al.	·		
	AC	4,404,265	09/13/83	Manasevit			
	AD	4,482,906	11/13/84	Hovel et al.			
	AE	4,523,211	06/11/85	Morimoto et al.			
	AF	4,661,176	04/28/87	Manasevit			
	AG	4,793,872	12/27/88	Meunier et al.			
	АН	4,846,926	07/11/89	Kay et al.			
	AJ	4,855,249	08/08/89	Akasaki et al.			
	ΑI	4,891,091	01/02/90	Shastry			
	AK	4,912,087	03/27/90	Aslam et al.			
	AL	4,928,154	05/22/90	Umeno et al.			
	АМ	4,963,949	10/16/90	Wanlass et al.			<u> </u>
	AN	5,141,894	08/25/92	Bisaro et al.			
	AO	5,159,413	10/27/92	Calviello et al.			
	AP	5,173,474	12/22/92	Connell et al.			
	AQ	5,221,367	06/22/93	Chisholm et al.			
	AR	5,225,031	07/06/93	McKee et al.			
	AS	5,358,925	10/25/94	Neville Connell et al.			
	AT	5,393,352	02/28/95	Summerfelt			
	AU	5,418,216	05/23/95	Fork			
	AV	5,450,812	09/19/95	McKee et al.			
	AW ———	5,478,653	12/26/95	Guenzer			
	4X	5,482,003	01/09/96	McKee et al.			
	AY	5,514,484	05/07/96	Nashimoto			
	4Z	5,556,463	09/17/96	Guenzer			
	3A	5,588,995	12/31/96	Sheldon			
		5,670,798	09/23/97	Schetzina			
-		5,733,641	03/31/98	Fork et al.			
		5,735,949	04/07/98	Mantl et al.			
		5,741,724	04/21/98	Ramdani et al.			
		5,810,923	09/22/98	Yano et al.			
		5,830,270	11/03/98	McKee et al.			
		5,912,068	06/15/99	Jia			
В		6,020,222	02/01/00	Wollesen			
В		6,045,626	04/04/00	Yano et al.			
→ B		6,064,078		Northrup et al.			
В		6,064,092		Park			
В		6,096,584	08/01/00	Ellis-Monaghan et al.			
Ві		6,103,008	08/15/00	McKee et al.	- -		
В		6,136,666	10/24/00	So			
ВІ		6,174,755	01/16/01	Manning	_		
W BO	Q K	5,180,486	01/30/01	eobandung et al.			

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Pr	CA	3,766,370	10/16/73	Walther		CLASS	IF APPRO	PRIATE	
1	СВ	4,006,989	02/08/77	Andringa					
	СС	4,284,329	08/18/81	Smith et al.		 			
	CD	4,777,613	10/11/98	Shahan et al.		 			
	CE	4,802,182	01/31/89	Thomton et al.					
	CF	4,882,300	11/21/89	Inoue et al.			<u>. </u>		_
	CG	4,896,194	01/23/90	Suzuki				-	
	СН	4,999,842	03/12/91	Huang et al.					_
	СІ	5,081,062	01/14/92	Vasudev et al.					_
	CI	5,155,658	10/13/92	Inam et al.					_
	СК	5,248,564	09/28/93	Ramesh					_
	CL	5,260,394	11/09/93	Tazaki et al.					
	СМ	5,270,298	12/14/93	Ramesh		-			_
	CN	5,286,985	02/15/94	Taddiken				<u> </u>	_
	СО	5,310,707	05/10/94	Oishi et al.					_
	СР	5,326,721	07/05/94	Summerfelt					_
	ca	5,404,581	04/04/95	Honjo			·		-
	CR	5,418,389	05/23/95	Watanabe			<u> </u>		\dashv
	cs	5,436,759	07/25/95	Dijaii et al.					ㅓ
	СТ	5,576,879	11/19/96	Nashimoto					\dashv
	CU	5,606,184	02/25/97	Abrokwah, et al.					\dashv
	cv	5,640,267	06/17/97	May et al.					ᅱ
	cw	5,674,366	10/07/97	Hayashi et al.				.	٦
	сх	5,729,641	03/17/98	Chandonnet et al.					\dashv
	CY	5,790,583	08/04/98	Но		+			\dashv
	cz	5,825,799	10/20/98	Ho et al.	-				\dashv
	DA	5,857,049	01/05/99	Beranek et al.					ᅦ
	DΒ	5,874,860	02/23/99	Brunel et al.					\dashv
	DC	5,926,496	07/20/99	Ho et al.					┨
	DD	5,937,285	08/10/99	Abrokwah, et al.	ĺ				7
	DE	5,981,400	11/09/99	Lo	1				╢
	DF	5,990,495	11/23/99	Ohba					┨
	DG	6,002,375	12/14/99	Corman et al.					\dashv
		6,008,762	12/28/99	Nghiem					┨
	DI	6,055,179	04/25/00	Koganei et al.					\dashv
		6,107,653	08/22/00	Fitzgerald					1
1		6,113,690		Yu et al.					1
	_	6,114,996	L	Nghiem					1
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		6,128,178		Newns					1
		6,143,072		McKee et al.					1
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	(GB	4,885,376	12/05/89	Verka	ide			
		GC	4,888,202	12/89	Mural	kami et al.			
		GD	4,891,091	12/90	Wanla	ass et al.			
		GE	5,051,790	09/24/91	Hamn	ner			
		GF	5,055,445	10/08/91	Belt e	t al.			
		GG	5,081,519	11/14/92	Nishir	nura et al.		1 -	
		GH	5,143,854	09/01/92	Pirrun	g et al.		1	
		GI	5,185,589	02/09/93	Krishr	naswamy et al.		<u> </u>	
		GJ	5,191,625	03/02/93	Gusta	vsson	_		
1		GK	5,194,397	03/16/93	Cook	et al.			
		GL	5,208,182	05/04/93	Naray	an et al.		-	
1	_	GМ	5,216,729	06/01/93	Berge	r et al.			
		GN	5,314,547	05/24/94	Heren	nans et al.	-		
		GO	5,352,926	10/04/94	Andre	ws			
		GP	5,356,509	10/18/94	Terran	ova et al.			
		GQ	5,371,734	12/06/94	Fische	er			
		GR	5,372,992	12/94	Itozaki	et al.			
	-	GS	5,405,802	04/11/95	Yamag	gata et al.		· · · · ·	
_		GT	5,442,561	08/15/95	Yoshiz	awa et al.			
		GU	5,453,727	09/26/95	Shibas	saki et al.			
		GV	5,466,631	11/14/95	Ichikav	va et al.			
\neg	-	gw	5,473,047	12/05/95	Shi		_		
		GX	5,473,171	12/95	Summ	erfelt			
		GY	5,479,033	12/26/95	Baca e	et al.		_	
		GZ	5,486,406	01/23/96	Shi		_		
		НА	5,491,461	1	Partin (et al.		-	
		нв	5,492,859		↓ _	uchi et al.			
_		нс	5,494,711		Takeda				
		HD :	5,504,035			er et al.			
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		HF \$	5,511,238	ll	Bayrak	taroglu			
		HG 5	5,512,773		Wolf et				
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EXAMINER TOUTIAL	IA	NUMBER 5.650.646	07/22/97	Summerfelt		CLASS	IF APPROPRIATE
196	IB	5,656,382	08/12/97				
-	IC	5,659,180	08/19/97	Nashimoto			
	ID	5,661,112	08/26/97	Shen et al.			
	IE .	5,679,965	11/95	Hatta et al.			
+	IF	5,725,641	03/10/98	Schetzina MacLeod			
+	IG	5,745,631	04/28/98	Reinker			
+	IH.	5,776,621	07/07/98				
 	11	5,777,350	07/07/98	Nashimoto			
 	lin L.	5,789,845	08/04/98	Nakamura et al.			
1	lk -	5,792,569	08/11/98	Wadaka et al. Sun et al.			
	JL.	5,792,679	08/11/98	Nakato			
-	IM	5,796,648	08/18/98	Kawakubo et al.			
+	IN	5,801,072	09/01/98				
+	10	5,812,272	09/22/98	Barber			·
+-	IP	5,814,583	09/98	King et al.			
_	iQ	5,825,055	10/20/98	Itozaki et al.			
_	iR	5,827,755	10/20/98	Summerfelt Yonchara et al.			
	IS	5,833,603	11/10/98	Kovacs et al.			
	IT	5,838,035	11/17/98	Ramesh			
	IU	5,844,260	12/01/98	Ohori			
_	IV	5,846,846	12/08/98	Suh et al.			
		5,863,326	01/26/99	Nause et al.			
		5,872,493	02/16/99	Ella			
		5,879,956	03/99	Seon et al.			
- 	Z	5,880,452	03/09/99	Plesko			
-1-1		5,883,564	03/16/99	Partin			
+		5,907,792	05/25/99	Droopad et al.			
-		5,937,274	08/10/99	Kondow et al.			
1-1		5,948,161		Kizuki			
		5,959,879		Koo			
 		5,966,323		Chen et al.			
- 		5,987,011		Toh			
- 		5,022,140		Fraden et al.			
- h		5,022,410		Yu et al.			
 		5,023,082		McKee et al.			
J.		6,028,853	<u> </u>	Haartsen			
- h		,049,702	 	Tham et al.			
		,078,717		Nashimoto et al			
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ATTY DOCKET NO. SERIAL NO. Form PTO 1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE 211147US99 09/903,784 **APPLICANT** LISTOER FERENCES CITED BY APPLICANT AROON TUNGARE ET AL **FILING DATE GROUP** FEB 1 4 2003 **JULY 13, 2001** 2826 **U.S. PATENT DOCUMENTS** EXAMINED INITIAL DOCUMENT SUB **FILING DATE** DATE **CLASS** NAME NUMBER **CLASS** IF APPROPRIATE FF MA 5,553,089 09/03/96 Seki et al. MB 5,528,057 06/18/96 Yanagase et al. MC 6,229,159 05/08/01 Suzuki MD 4,748,485 05/31/88 Vasudev ME 4,984,043 01/08/91 Vinal MF 5,754,319 05/19/98 Van De Voorde et al. MG 6,108,125 08/22/00 Yano МН 5,073,981 12/17/91 Giles et al. MI 5,140,651 08/18/92 Soref et al. MJ 5,610,744 03/11/97 Ho et al. MK 6,362,017 03/26/02 Manabe et al. ML 6,242,686 06/05/01 Kishimoto et al. MM 5,689,123 11/18/97 Major et al. MN 5,670,800 09/23/97 Nakao et al. MO 5,067,809 11/26/91 Tsubota MP 5,596,205 01/21/97 Reedy et al. MQ 6,175,555 01/16/01 Hoole MR 5,357,122 10/18/94 Okubora et al. MS 4,084,130 04/11/78 Holton MT 6,093,302 07/25/00 Montgomery MU 6,372,813 04/16/02 Johnson et al. ΜV 5,608,046 03/04/97 Cook et al. MW 5,955,591 imbach et al. 09/21/99 MX 6,022,963 02/08/00 McGall et al. MY 6,083,697 07/04/00 Beecher et al. MZ 5,063,081 11/05/91 Cozzette et al. NA 5,479,317 12/26/95 Ramesh 5,306,649 NB Hebert 04/26/94 NC 5,962,069 10/05/99 Schindler et al. ND 5,541,422 07/30/96 Wolf et al. NE 5,873,977 02/23/99 Desu et al. NF 5,538,941 07/23/96 Findikoglu et al. NG 6,046,464 04/04/00 Schetzina NH 6,235,145 05/22/01 Li et al. NI 5,610,744 03/11/97 Ho et al. NJ 5,280,013 01/18/94 Newman et al. NK 6,348,373 B1 02/19/02 Ma et al. 6,339,664 B1 NL 01/15/02 Farjady et al. NM 4,439,014 03/27/84 Stacy et al. NN 4,889,402 12/26/89 Reinhart NO 5,963,291 10/05/99 Wu et al. NP 6,011,641 01/04/00 Shin et al. NQ 6,340,788 B1 01/22/02 King et al.

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EXAMINER		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
RE	OA	5,807,440	09/15/98	Kubota et al.			
	ОВ	4,681,982	07/21/87	Yoshida			
	ОС	4,629,821	12/16/86	Bronstein-Bonte et al.			
	OD	4,452,720	06/05/84	Harada et al.			
	OE	3,935,031	01/27/76	Adler			
	OF	5,760,426	06/02/98	Marx et al.			
	OG	5,053,835	10/01/91	Horikawa et al.			
	ОН	6,326,645 B1	12/04/01	Kadota			
	OI	5,770,887	06/23/98	Tadatomo et al.			
	Ol	6,372,356 B1	04/16/02	Thornton et al.			
	ок	4,774,205	09/27/88	Choi et al.			
	OL	6,359,330 B1	03/19/02	Goudard			
	ОМ	5,312,765	05/17/94	Kanber			
	ON	5,734,672	03/31/98	McMinn et al.			
	00	6,367,699 B2	04/09/02	Ackley			
	OP	5,530,235	06/25/96	Stefik et al.			
	ΟQ	5,623,552	04/22/97	Lane			
	OR	5,481,102	01/02/96	Hazelrigg, Jr.			
	os	6,134,114	10/17/00	Ungermann et al.			
	ОТ	5,984,190	11/16/99	Nevill			
	ου	5,789,733	08/04/98	Jachimowicz et al.			
	ov	5,753,300	05/19/98	Wessels et al.			
	ow	6,208,453	03/27/01	Wessels et al.			
	ОХ	5,886,867	03/23/99	Chivukula et al.			
	OY	5,028,976	07/02/91	Ozaki et al.			
	oz	5,869,845	02/09/99	Vander Wagt et al.			
	PA	5,596,214	01/21/97	Endo			
	PB	6,391,674 B2	05/21/02	Ziegler			
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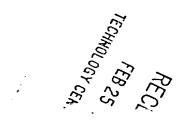
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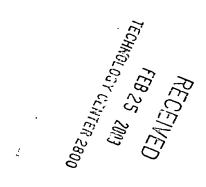
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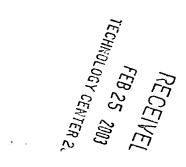


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